

Large Area Nanogratings

- 1 D
- rectangular
- hexagonal

Application:

- Master for Imprint Templates
- Microoptics
- NanoBio Technology
- Measurement

AMO offers gratings fabricated by inhouse interference lithography (IL). The IL technology allows producing large, coherent and periodic gratings with nearly constant pitch. Pattern transfer and further processing can be carried out according to customer requirements. Substrates up to 6 inch and any rectangular within.

Process Control:

All grating dimensions are specified and controlled during and after processing. Line width maps, LER characterisation and defect inspection are available on request.

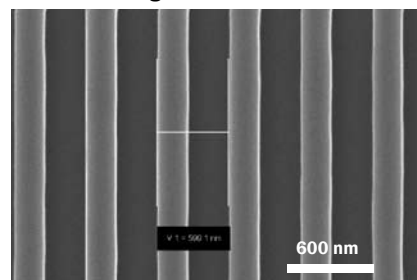
Specification:

| | |
|---------------------|--|
| Substrate material | Silicon or fused silica |
| Substrate thickness | Typical 500 µm to 650 µm |
| Substrate size | Up to 6 inch and any rectangular within. |
| Grating pitch | 180 nm to 2500 nm |
| Etch depth | 90 nm to 2500 nm |
| Line width | 40 nm to 1500 nm |
| Active grating area | Up to 140 mm in diameter |

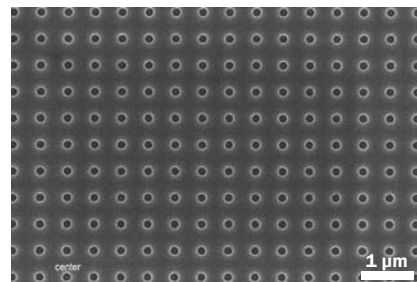
Some specifications are matter of negotiation. For further details please contact us.

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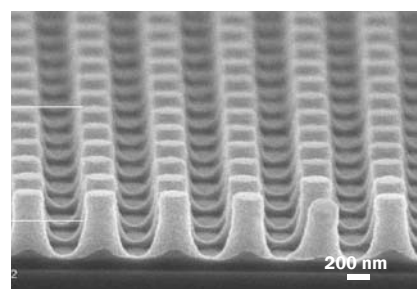
Linear Gratings



Hole Pattern



Pillar Pattern



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